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**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants:	Takasu et al.	Examiner:	John S Y Chu
Serial No.:	10/603,511	Group Art Unit:	1752
Confirmation No:	3638	Docket:	105-86 PCT/US
Filed:	June 25, 2003	Dated:	June 29, 2004
For:	NEGATIVE RESIST COMPOSITION		

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

*I hereby certify this correspondence is being deposited with the United States Postal Service as first class mail, postpaid in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450 on June 29, 2004*

Signed: Kathleen A. Sandoz

**RESPONSE TO RESTRICTION REQUIREMENT**

Sir:

In the Office Action mailed June 10, 2004, the Examiner has imposed a Restriction Requirement to one of the following inventions under the provisions of 35 U.S.C. §121:

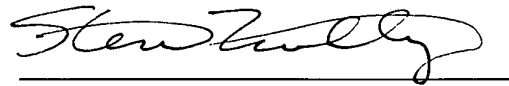
- I. Claims 1-23, drawn to a resist composition, classified in class 430, subclass 270.1; and
- II. Claim 24, drawn to a method of forming a pattern, classified in class 430, subclass 326.

In response to the Restriction Requirement, Applicants elect the subject matter defined by Claims 1-23 in Group I without traverse. Applicants reserve the right to pursue the claim of Group II in a divisional application.

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In view of the present election, it is believed that this application is in condition for further consideration and examination. If resolution of any remaining issues are required prior to examination of the application, it is respectfully requested that the Examiner contact Applicants' undersigned attorney at the telephone number provided below.

Respectfully submitted,



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